

Freeform Search

Database: US Pre-Grant Publication Full-Text Database
 US Patents Full-Text Database
 US OCR Full-Text Database
 EPO Abstracts Database
 JPO Abstracts Database
 Derwent World Patents Index
 IBM Technical Disclosure Bulletins

Term: l10 and (acid or acidic or ph) with (silica or silicon or "sio.sub.2" or sio2 or abrasive) and (basic or alkali or ph) near substance


Display: **Documents in Display Format:** **Starting with Number**

Generate: ☐ Hit List ☒ Hit Count ☐ Side by Side ☐ Image

Search History

DATE: Tuesday, October 02, 2007 [Purge Queries](#) [Printable Copy](#) [Create Case](#)

<u>Set</u> <u>Name</u> <u>Query</u> <small>side by side</small>	<u>Hit</u> <u>Count</u>	<u>Set</u> <u>Name</u> <small>result set</small>
<i>DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>		
<u>L14</u> l10 and (acid or acidic or ph) with (silica or silicon or "sio.sub.2" or sio2 or abrasive) and (basic or alkali or ph) near substance	7	<u>L14</u>
<u>L13</u> l12 not l11	17	<u>L13</u>
<u>L12</u> l10 and (acid or acidic or ph) with (silica or silicon or "sio.sub.2" or sio2 or abrasive) and (basic or alkali or ph) near solution	59	<u>L12</u>
<u>L11</u> l10 and (acid or acidic or ph) near4 (silica or silicon or "sio.sub.2" or sio2 or abrasive) and (basic or alkali or ph) near solution	42	<u>L11</u>
<u>L10</u> bulk density and (fumed or fume) (silica or silicon or "sio.sub.2" or sio2) and (polishing or planarizing or planarization or abrasive or cmp or polish)	264	<u>L10</u>
<u>L9</u> L8 and bulk density	2	<u>L9</u>
<u>L8</u> L7 and (fumed or fume) (silica or silicon or "sio.sub.2" or sio2)	95	<u>L8</u>
<u>L7</u> (acid or acidic or ph) near4 silica and (polishing or planarizing or planarization or abrasive or cmp or polish).ti. and (basic or alkali or ph) near solution	247	<u>L7</u>
<i>DB=PGPB,USPT; PLUR=YES; OP=ADJ</i>		
<u>L6</u> l3 and l5	0	<u>L6</u>

 L5 5116535.pn. or 5246624.pn. or 6248144.pn. or 6409780.pn. 4 L5

L4 20020028636 or 20040040217 or 5116535.pn. or 5246624.pn. or 6248144.pn. or 6352679.pn. or 5904159.pn. 7 L4

L3 (acid or acidic) near4 silica and (polishing or planarizing or planarization or abrasive or cmp or polish).ti. and (basic or alkali) solution 32 L3

DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ

L2 L1 and (acid or acedic) fumed silica 1 L2

(polishing or planarizing or planarization or abrasive or cmp or polish).ti. and (abrasive or silica or silicon dioxide or silicon oxide or (polishing or planarizing or planarization or cmp) (particle or particulate or grit or grain)) with (volume or vol or "vol." or "vol.%" of "vol%") with (size or diameter) with (nm or nanometer)

L1 68 L1

END OF SEARCH HISTORY